

3D electronics for hybrid pixel detectors

ATLAS read-out chip upgrade

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3D for hybrid pixel detectors

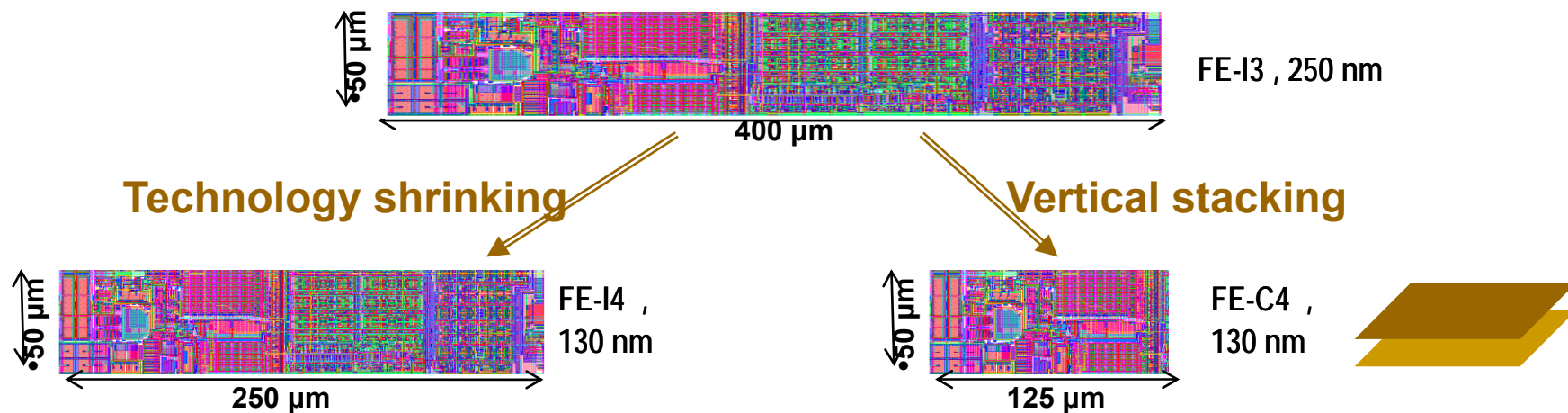
Atlas read-out chip upgrade

- 3D FE-TC4 project :
 - Motivations
 - Context
 - Steps : 2D and 3D circuits
- 2D test results
- 3D design
 - Technology description
 - Tiers description
 - Final assembly
- Conclusion & futures plans

3D motivations for ATLAS upgrades

- Improve spatial resolution
- Deal with an increasing counting rate
- ➔ Decrease pixel size

3D pixel road map (A.Rozanov, ATLAS-France Paris, June 22, 2009) :



- 3D benefits :**
- Pixel size reduction
 - Pixel functionalities splitting
 - Technologies mixing

FETC4 – Atlas 3D read-out chip project

Bonn, CPPM, and LBL collaboration

- Goal : to reach a pixel dimension of $50 \times 125 \mu\text{m}$
- Solution :
 - split pixel functionalities into 2 parts
 - stack vertically these 2 “tiers”
- Context / Opportunity :
 - Interest (and funding !) of IN2P3 on 3D electronics
 - First MPW run for High Energy Physics organized by FNAL with a consortium of 15 institutes (France, Germany, Italy, Poland and United-States)
 - This process combines :
 - **Chartered 130nm technology**
 - **Tezzaron 3D technology**

3D project steps

FEI4_P1 design 14*61 "analog" pixel matrix (50 * 166µm)
(8 metal levels, 130nm, IBM)

→ Translation into 2D Chartered technology

(8 metal levels, 130nm) : **FEC4_P1**

- Pixel structure : identical to FEI4_P1
- Objective : test Chartered technology (functionalities, performances, radiation...)



First 3D design : **FETC4_P1**

Chartered (5 metal levels , 130nm) + Tezzaron

- One tier for the analogue pixel part,
- One tier for the digital

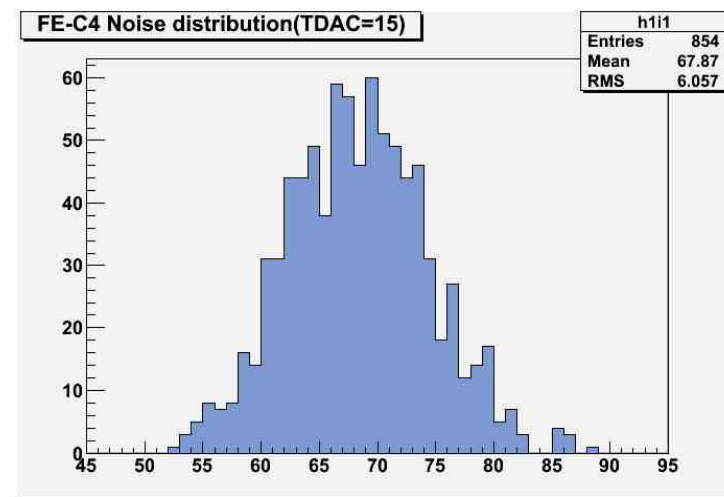
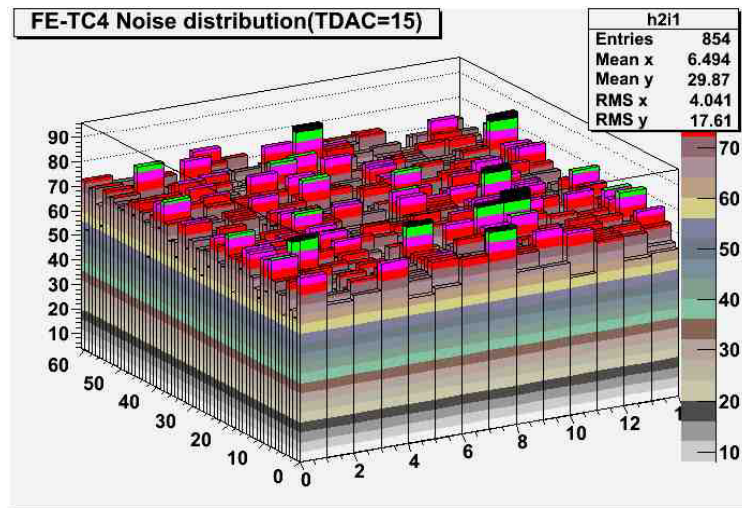
Submission:
March 08
Test:
Summer 08

Submission:
February 09
Test:
April 09

Submission:
Summer 2009

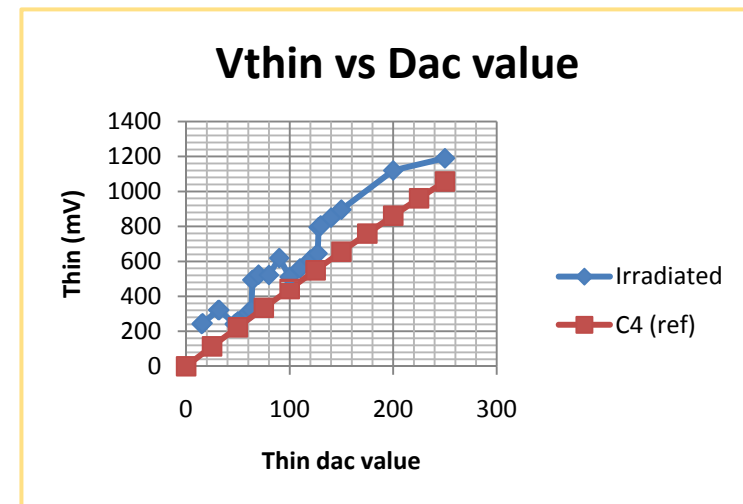
FEC4_P1 test results

- Due to schedule no optimization of transistors has been done
- Surprisingly, main results are equivalent to IBM ones
 - Threshold min around 1100 e-
 - Un-tuned threshold dispersion 200 e-
 - Noise lower than 80 e-



FEC4_P1 test results : Irradiations

- Irradiation performed at CERN/PS facility (24 GeV protons) up to 400 MRad
 - Problem discovered after 160 MRad on latches (output tends to be blocked in "1" state)
 - Difficult to work with the circuit by after
 - Problem reproduced in simulation "corners"
... but
- Analog is still working** even with increased of noise : 250 e- (threshold dispersion is meaningless)

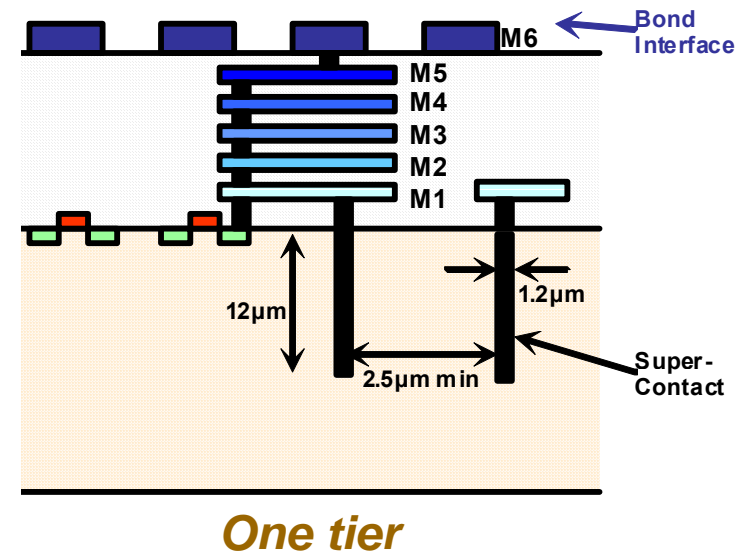
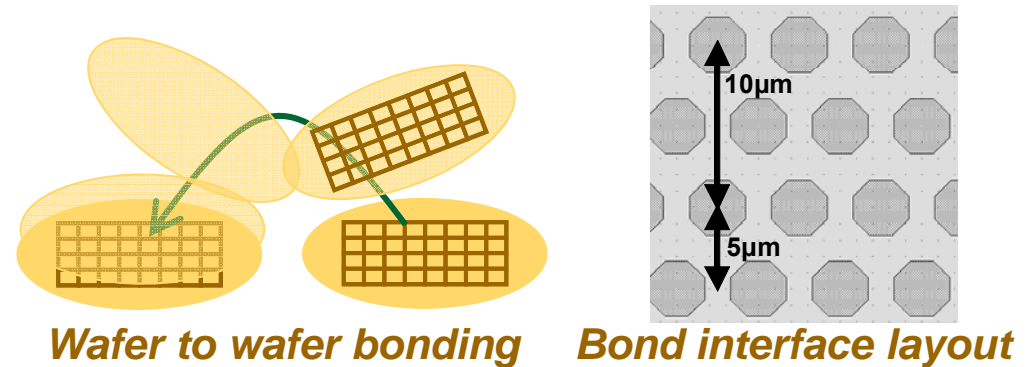


Tezzaron-Chartered 3D technology :

Vertical integration

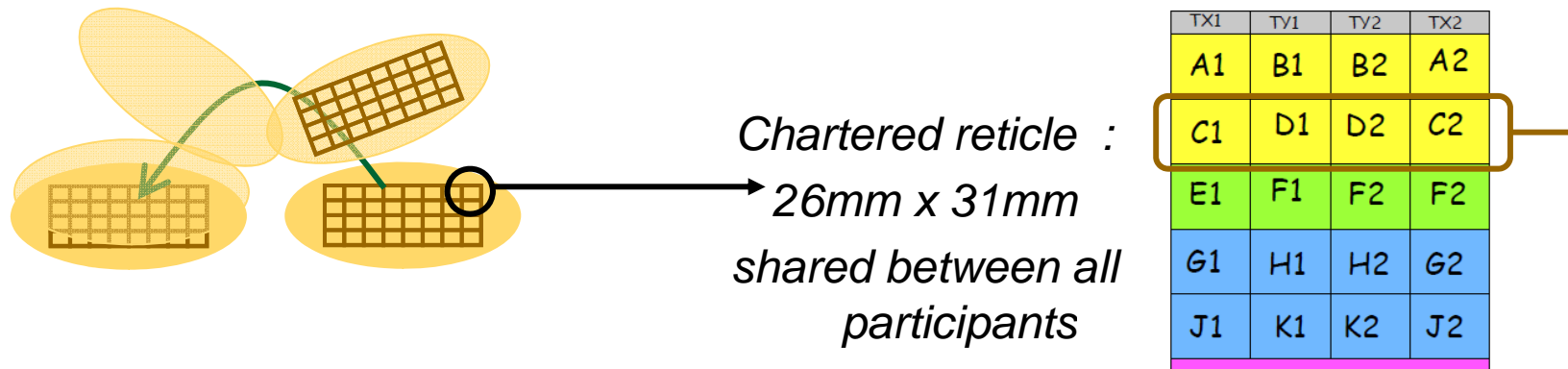
Characteristics :

- 2 wafers (tier 1 and tier 2) are stacked face to face with Cu-Cu thermo-compression
- Via First technology : Super-Contacts (Through Silicon contacts) are formed before the BEOL of Chartered technology.
- Wafer is thinned to access Super-Contacts
- Back-side metal for bonding (after thinning)



Chartered-Tezzaron MPW run

- 2 identical wafers are stacked => tier 1 and tier 2 are in the same reticle

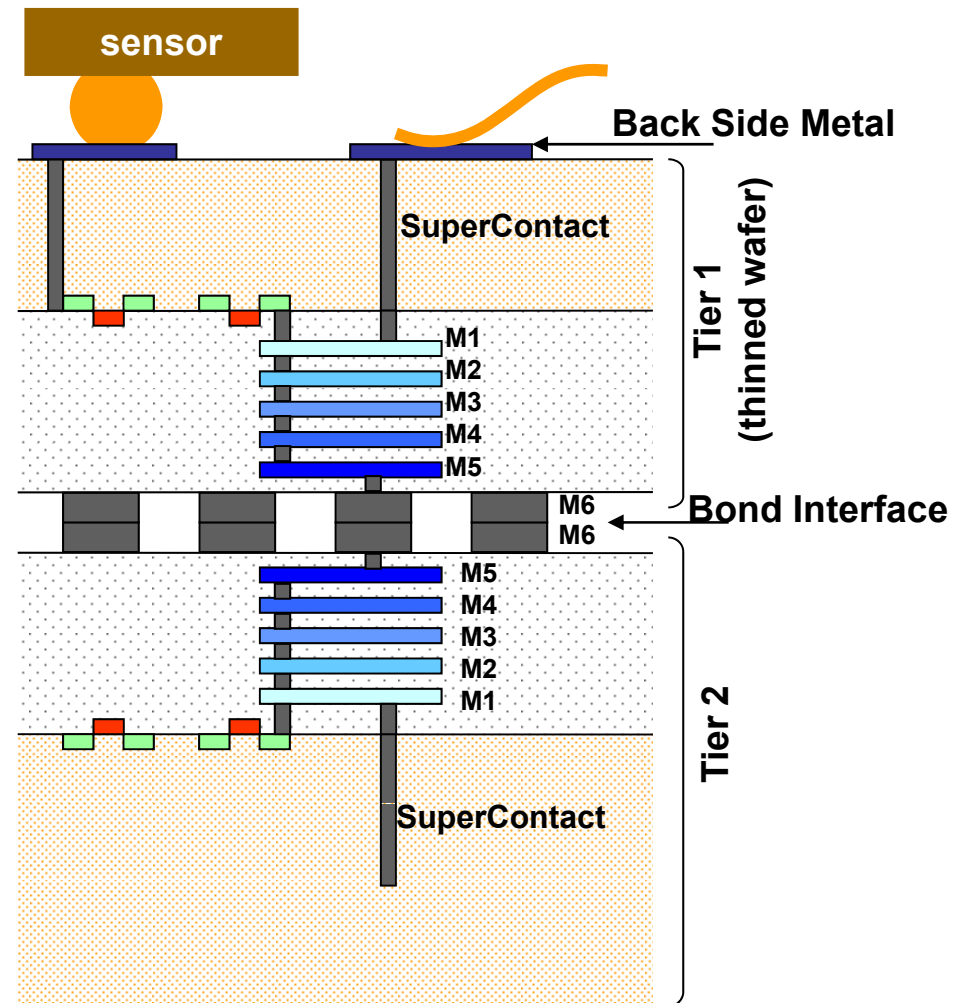


4 sub-reticles for SLHC chips projects : FE_TC4_P + OmegaPix

- C1, D1 = analog tier “FE-TC4-AE” + analog OmegaPix
- C2 = first version for digital tier : FE-TC4-DS
- D2 = second version for digital tier : FE-TC4-DC
read-out structure “FEI4-like”+ digital OmegaPix

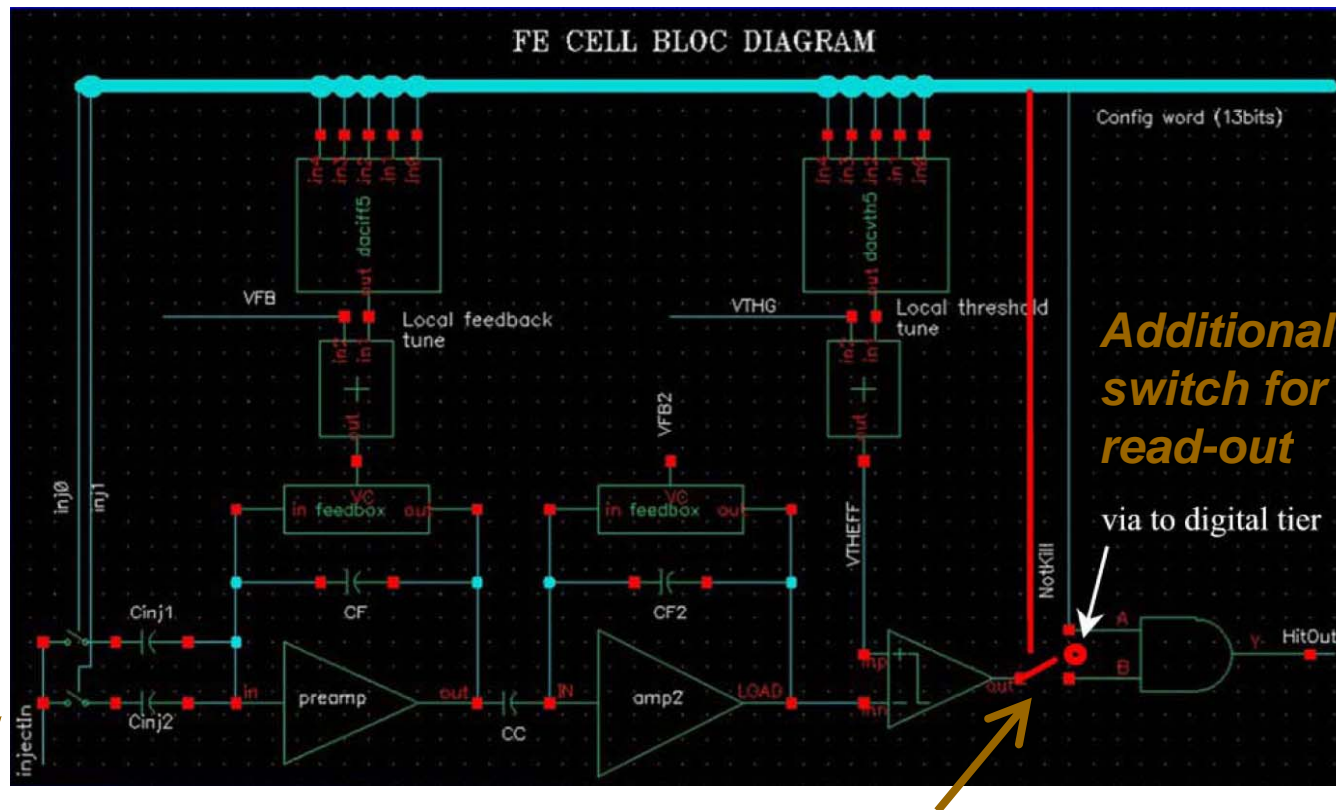
Chartered-Tezzaron MPW run

- Tier 1 (analog) is thinned to access Super-Contacts.
- I/O of the tiers are independent, each tier can be tested separately
- Analog tier has been kept as close as possible identical to FE_C4, main change is the reduction to 5 metal layers



FE-TC4-AE analogue tier

- Based on FEI4_P1 pixel



Input signal from sensor, via Super-Contacts

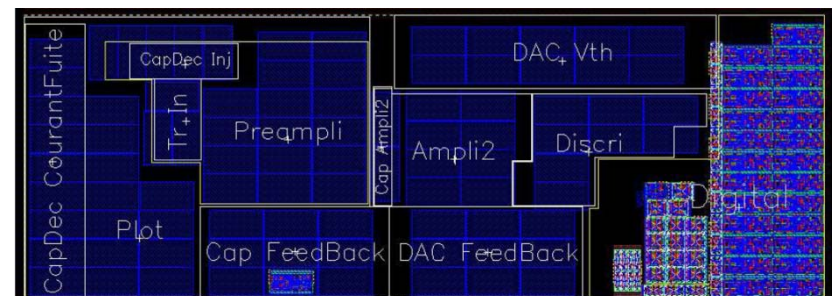
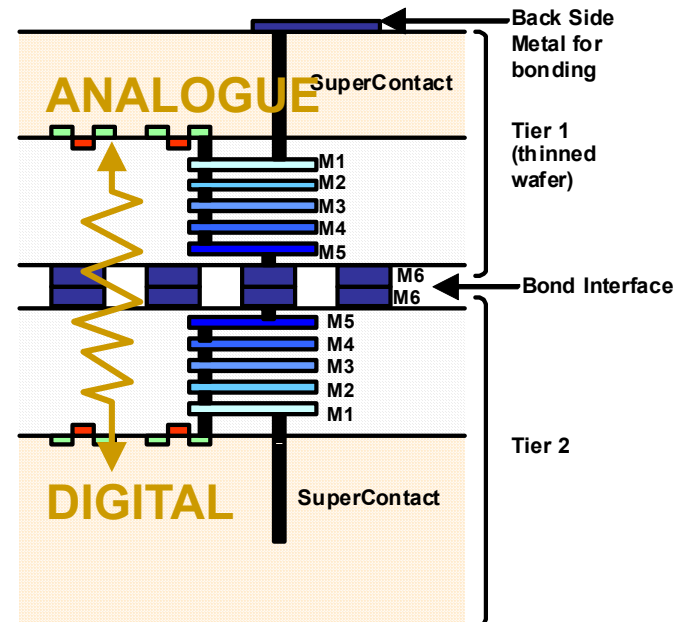
2 possible ways for discriminator output read-out:

- **With the simple read-out part existing yet into the pixel**
- **With the tier 2 (via the Bond Interface)**

FE-TC4-DS digital tier dedicated for test

Parasitic coupling study between tier

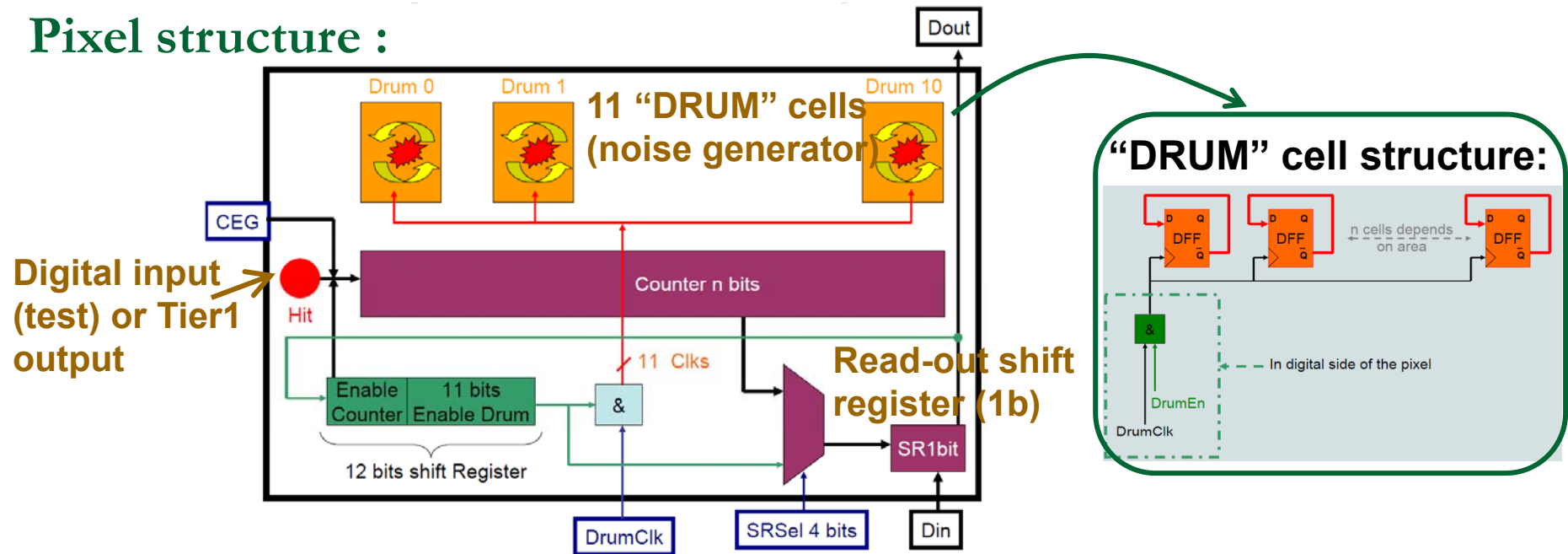
- Analogue tier and digital tier are face to face (sensitive part facing digital part).
- FE-TC4-DS : dedicated for parasitic coupling studies between the 2 tiers.
- 3 functions :
 - Read the discriminator output
 - Generate noise (digital commutations) in front of 11 specific areas of the analogue pixel (preamplifier, feed-back, amplifier2, DAC...)
 - Test different shielding configurations.



Analogue pixel layout : 11 specific areas

FE-TC4-DS digital tier dedicated for test

Pixel structure :



Shielding strategy :

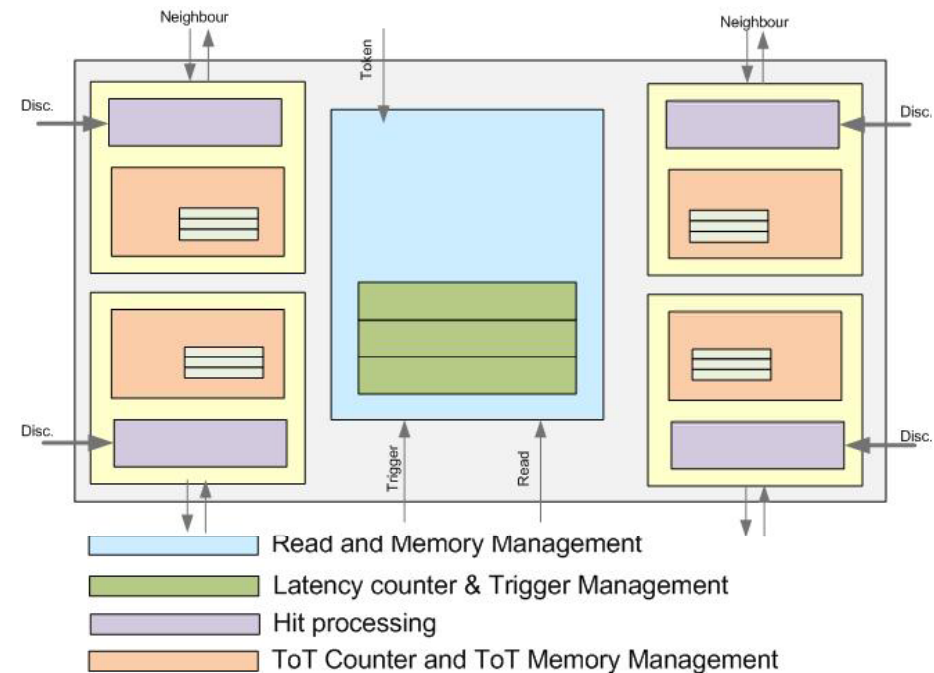
- 5 columns without any shielding (reference),
- 4 columns with shielding in metal 5,
- 2 columns with shielding in metal 3,
- 2 columns with both shielding.

FE-TC4-DC digital tier

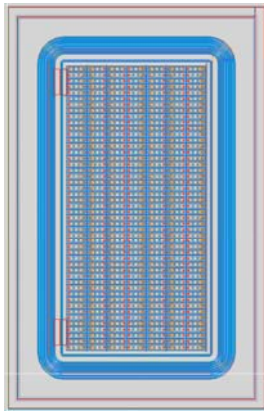
Complex read-out chip

Read-out chip similar to what is foreseen for FE-I4:

- **4-pixel region :**
 - 61 pixels/ column => implies 31 '4-pixel' regions plus 2 dummy pixels per double-column.
- **Simplified periphery and read-out control logic :**
 - Some signals are provided from the outside (data read-out signals, signals for pixel hits communication to the periphery...

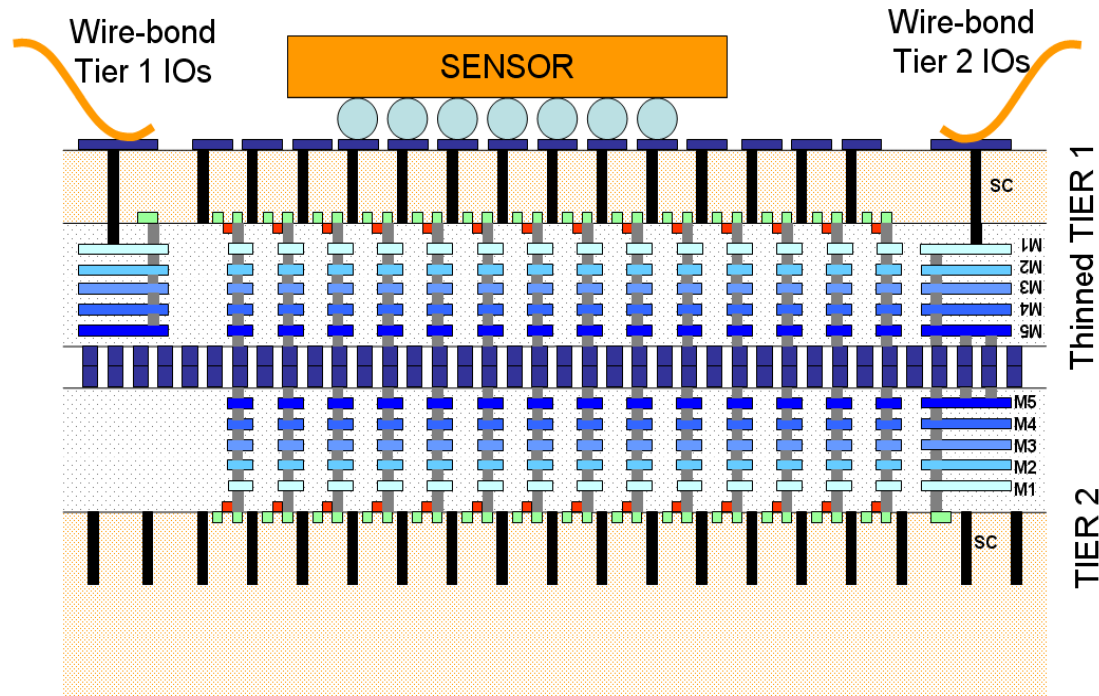


Final assembly with sensor



Sensor layout :

Anna Macchiolo, Max-Planck-Institut für Physik, Munich



Bonding foreseen to be done at IZM (Berlin) as for ATLAS modules

Due to geometric constraints, sensor matrix is reduced :

- ❑ Sensor matrix : 7 columns of 48 pixels
- ❑ Tier 1 and Tier 2 matrix : 14 columns of 61 pixels

Conclusions and future plans

- Benefits of 3D technology for hybrid pixel detectors appear evident :
 - Pixel size reduction
 - Technologies mixing
 - More functionalities can be implemented in front of the analogue pixel
- By the end of the year :
 - Tests will be performed on FETC4_P1
 - Design and production of FEC4_P2 (transistor optimization and few minor corrections) , submission beginning of November
 - Start working to design a full scale FETC4

Conclusions and future plans (con't)

■ FE_C4 chip

- Chip size the 18.8 x 20.1 mm (336 rows x 160 columns, EOC 1.95 mm)
- Pixel pitch 50*125 μm , same technology as FE_TC4_P1
- Bump bond pads compatible with 250 μm sensor pitch
- Keep the possibility of different flavors in some columns
- **Pros:** FE_I4 blocks reuse, compatibility with FE_I4 chip for sensors, bump bonding , module/stave integration, testing tools, software, mechanics
- **Cons:** cost -> Needs 2 sets of mask (the chip cannot fit in $\frac{1}{2}$ reticle)

Run foreseen by first half of 2010

ALL GROUPS INTERESTED IN SHARING THIS RUN ARE WELCOME

(50 % of the reticle area is available)